



Session Title:	[WeD2] Lithography Process II
Session Date:	November 13 (Wed.), 2024
Session Time:	14:10-16:10
Session Room:	Room D (Sidney Room, 2F, Paradise Hotel Busan)
Session Chair:	Prof. Su-Mi Hur (Chonnam Nat'l Univ., Korea)

[WeD2-1] [Invited]

14:10~14:40

Layer-Ordered Organotin Clusters for Extreme-Ultraviolet Photolithography

Youngmin You (Yonsei Univ., Korea)

[WeD2-2] [Invited]

14:40~15:10

Improvement of EUV Resist Performance through EUV Underlayers

Jungyoul Lee, Jaehyun Kim, Myounghyun Hur, Dongkyu Ju, and Taeik Kim (DONGJIN SEMICHEM Co., Ltd., Korea)

[WeD2-3] [Invited]

15:10-15:40

Enhancing EUV Lithography with Directed Self-Assembly: Defect Correction and Pattern Quality Improvement

Su-Mi Hur (Chonnam Nat'l Univ., Korea)

[WeD2-4] [Invited]

15:40-16:10

Biologically-Inspired Optic Designs for Advanced Imaging Systems

Young Min Song (GIST, Korea)